

AP20100505019 MAY 2006

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Masanori NAKAMURA et al.

Application No.: Not Yet Assigned

Confirmation No.: N/A

Filed: Concurrently Herewith

Art Unit: N/A

For: POSITIVE PHOTORESIST AND METHOD
FOR PRODUCING STRUCTURE

Examiner: Not Yet Assigned

INFORMATION DISCLOSURE STATEMENT (IDS)

MS PCT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Submitted herewith on Form PTO-1449 or PTO/SB/08 is a listing of documents known to Applicant in order to comply with Applicant's duty of disclosure pursuant to 37 CFR 1.56. Applicant respectfully requests that the listed documents be considered by the Examiner and formally be made of record in the present application and that an initialed copy of Form PTO-1449 or PTO/SB/08 be returned in accordance with MPEP §609.

As provided in 37 CFR §1.98(d), copies of the documents are not being provided since they were previously cited by or submitted to the Patent Office in parent application Serial No. _____, filed _____.

A copy of each listed document, that was cited in the International Search Report or International Preliminary Examination Report attached hereto, should have been provided to the U.S. Patent and Trademark Office by the WIPO, and the provisions of 37 CFR §§1.97 and 1.98 should have been complied with. Copies of the references cited in the specification are also enclosed.

The submission of any document herewith, which is not a statutory bar, is not intended as an admission that such document constitutes prior art against the claims of the present application or that such document is considered material to patentability as defined in 37 CFR §1.56(b). Applicant does not waive any rights to take any action which would be appropriate to antedate or otherwise remove as a competent reference any document which is determined to be a *prima facie* prior art reference against the claims of the present application.

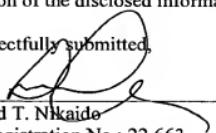
1AP20 Rec'd PTO 19 MAY 2006

1. This Information Disclosure Statement is being filed within three months of the U.S. filing date or within three months from the date of entry of the national stage as set forth in 37 C.F.R. §1.491 in compliance with 37 C.F.R. §1.97(b), OR is being filed concurrent with filing of the Continued Prosecution Application (CPA) or the Request for Continued Examination (RCE). No fee is required (37 C.F.R. §1.97(b)).

2. Please charge any fee deficiency or credit any overpayment to Deposit Account No. 18-0013 as needed to ensure consideration of the disclosed information.

Dated: May 19, 2006

Respectfully submitted,

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Substitute for form 1449A/B/PTO

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet	1	of	1	Attorney Docket Number	MIY-0211
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U.S. PATENT DOCUMENTS					
Examiner Initials ¹	Cite No. ¹	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
/ACW	AA	6,200,727	3-13-2001	URANO et al.	
/ACW	AB	5,645,969	7-8-1997	MATSUO et al.	
/ACW	AC	5,674,657	10-7-1997	TAN et al.	
/ACW	AD	5,652,081	7-29-1997	TAN et al.	

FOREIGN PATENT DOCUMENTS					
Examiner Initials	Cite No. ¹	Foreign Patent Document Country Code ³ -Number-Kind Code ⁴ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
/ACW	BA	11-288089	10-19-1999	MITSUBISHI CHEMICAL CORP	
	BB	09-160236	6-20-1997	MITSUI TOATSU CHEM INC	
	BC	08-184964	7-16-1996	MITSUBISHI CHEM CORP	
	BD	10-186650	7-14-1998	FUJI PHOTO FILM CO LTD	
	BE	2000-292927	10-20-2000	HITACHI LTD HITACHI CHEM CO LTD	
	BF	11-338143	12-10-1999	HITACHI CHEMICAL DUPONT MICROSYSTEMS LTD	
	BG	11-223942	8-17-1999	MITSUBISHI CHEMICAL CORP	
	BH	09-146269	6-6-1997	FUJI PHOTO FILM CO LTD	
	BI	09-015851	1-17-1997	FUJI PHOTO FILM CO LTD	
	BJ	08-314142	11-29-1996	SHIPEL CO LTD LIABILITY CO	
/ACW	BK	2001-183838	7-6-2001	HITACHI CHEM CO LTD	

¹EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. ²Applicant's unique citation designation number (optional). ³See Kind Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ⁴Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁵For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁶Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁷Applicant is to place a check mark here if English language Translation is attached.

NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			
/ACW	CA	International Search Report dated March 1, 2005			

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²Applicant's unique citation designation number (optional). ³Applicant is to place a check mark here if English language Translation is attached.

Examiner Signature	/Amanda C. Walker/	Date Considered	11/30/2008
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